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ME	EP 0684637	11/29/95	EP	—	—	
ME	EP0637063	2/1/95	EP	—	—	

ME	XP000687427-YOSHIMARU M ET AL "HIGH QUALITY ULTRA THIN ..." DECEMBER 13, 1992 Pgs 271-274
ME	XP000297634-THERMAL NITRIDATION OF SILICON IN A CLUSTER TOOL-JANUARY 20, 1992 Pgs 341-343
ME	Yoshimaru, Inoue, Itoh, Kurogi, Tamura, Hirasita, Ichikawa and Ino, High Quality Ultra Thin Si_3N_4 Film Selectively Deposited on Poly-Si Electrode by LPCVD with in Situ HF vapor Cleaning, Dec. 13, 1992, IEDM 92-271
ME	DeLino, Fair and Salimian. Thermal Nitridation of silicon in cluster tool. Applied

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